

NAR Labs
國家實驗研究院

PIII機台簡介

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PULSION[®] is the Plasma Immersion Ion Implanter (PIII) designed by IBS. PULSION'S[®] unique polarization mode and pulsed plasma configuration provides the capability to achieve very low implantation depths and to achieve conformal doping.

Furthermore, its high current capability delivers high dose implantation at a very low cost.

